

Sub D1

1. (Twice Amended) An embedded electroconductive layer comprising:
any one of an opening part or a depressed part formed in an insulating film on a substrate;
a barrier layer covering said opening part or said depressed part;
a metal growth promoting layer on said barrier layer, said metal growth promoting layer being made of a material different from that of said barrier layer; and
an electroconductive layer embedded in said opening part or said depressed part via said barrier layer and said metal growth promoting layer.

Sub F3

5. (Twice Amended) An embedded electroconductive layer comprising:
any one of an opening part or a depressed part formed in an insulating layer on a substrate;
a ground layer containing oxygen at a high concentration in the lower part thereof and at a low concentration in the upper part thereof, and said ground layer covering the surface of said insulating film in said opening part or said depressed part; and
an electroconductive layer embedded in said opening part or said depressed part via said ground layer.